

Atty. Dkt. No. 039153-0306 (F0793)

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1 1. - 6. (Cancelled)

1 7. (Currently Amended) A method of manufacturing an
2 integrated circuit, the method comprising:
3 providing a pattern of radiation via an LCD or LED assembly
4 in response to a control signal from a computer, the computer generating
5 the control signal in response to image data stored in a database, the
6 computer ~~generating~~ executing software to select a component, and
7 generating data from the image data to generate the control signal from
8 the image data associated with the component; and
9 performing a semiconductor fabrication process in
10 accordance with the pattern of radiation.

1 8. (Original) The method of claim 7, further comprising:
2 providing a second pattern of radiation via the LCD or LED
3 assembly; and
4 performing a second semiconductor fabrication process in
5 accordance with the second pattern of radiation.

1 9. (Original) The method of claim 7, wherein the pattern is
2 provided to a wafer in a step and repeat process.

1 10. (Original) The method of claim 7, wherein the pattern is
2 representative of a metal layer associated with the integrated circuit.

1 11. (Original) The method of claim 7, wherein the pattern is
2 representative of a structure associated with a transistor for the integrated
3 circuit.

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1 12. (Previously Amended) The method of claim 7, wherein a
2 the component data is related to interconnect layers.

1 13. (Original) The method of claim 7, wherein the integrated
2 circuit is an ASIC.

1 14. (Original) The method of claim 7, wherein the pattern is
2 provided via the LCD assembly.

1 15. - 20. (Cancelled)
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1 21. (Currently Amended) A method of using a pattern
2 generator for an integrated circuit fabrication system, the method
3 comprising:
4 providing a pattern of radiation via an LCD assembly in
5 response to a control signal from a computer, the computer generating the
6 control signal in response to image data stored in a database, the
7 computer executing software to select a generating component data from
8 the image data to generate and generating the control signal from the
9 image data associated with the component; and
10 performing a semiconductor fabrication process in
11 accordance with the pattern of radiation.

1 22. (Previously Added) The method of claim 21, wherein the
2 pattern is for an ASIC device.

1 23. (Previously Added) The method of claim 22, wherein in the
2 pattern generator further comprises:
3 means for providing a pattern of light;

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4 means for controlling the means for providing, wherein the
5 means for controlling selects the pattern; and
6 means for focusing the light on a wafer.

1 24. (Previously Added) The method of claim 15, wherein the
2 image data are shapes representing component interconnects.

1 25. (Previously Added) The method of claim 23, wherein the
2 means for controlling includes a workstation executing a software
3 program.

1 26. (Previously Added) The method of claim 25, wherein the
2 means for providing a pattern includes liquid crystals.

1 27. (Currently Amended) In a lithographic system for an
2 integrated circuit fabrication process, the lithographic system including a
3 computer and a configurable mask or reticle coupled to the computer,
4 wherein the configurable mask or reticle allows light to be transmitted in a
5 pattern controlled by a control signal from the computer, a method
6 comprising:

7 providing a pattern of radiation via the configurable mask or
8 reticle in response to a control signal from a computer, the computer
9 generating the control signal in response to image data stored in a
10 database, the computer using executing software to select a component
11 data from the image data to generate the control signal in response to the
12 image data associated with the component; and
13 performing a semiconductor fabrication process in
14 accordance with the pattern of radiation.

1 28. (Previously Added) The method of claim 27, wherein the
2 configurable mask or reticle is an LCD or LED matrix.

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1 29. (Previously Added) The method of claim 27 wherein the
2 image data includes ASIC information.

1 30. (Previously Added) The method of claim 29, wherein the
2 database is stored on a storage media.

1 31. (Previously Added) The method of claim 27, wherein the
2 image data is related to transistor structures.

1 32. (Previously Added) The method of claim 27, wherein the
2 control signal is a video signal.

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cont.